

## **Advanced Energy Unveils Aera(R) PI-980(TM) Pressure-Insensitive MFC With NeuralStep(TM) Control Technology**

Fort Collins, Colorado (ots/PRNewswire) -

- Next-Generation Pressure-Insensitive MFC for Etch, CVD, PVD and Diffusion Processes Enables Exceptionally Fast Response and Higher Yields

Advanced Energy Industries, Inc. (Nasdaq: AEISE) today unveiled its next-generation Aera(R) PI-980(TM) series of pressure-insensitive mass flow controllers (MFCs) for advanced semiconductor applications. Designed to improve processes for etch, CVD, PVD and diffusion, the PI-980 MFC's innovative technology provides greater gas-flow stability, higher accuracy, exceptionally fast response and superior real-time process control. Its highly stable flow delivers greater process control and repeatability, maximizing production yields.

(Logo: <http://www.newscom.com/cgi-bin/prnh/20030825/AEISLOGO>)

The PI-980 series complements the recently released Aera Transformer(TM) 780/7800 series of digital MFCs, allowing fabs and OEMs to standardize on the latest technologies from Aera across multiple process steps and varied application requirements.

By combining exceptionally fast NeuralStep(TM) control technology with an integrated pressure transducer, the PI-980 MFC dramatically increases the speed of the MFC response. This increased speed virtually eliminates the effects of upstream and downstream pressure disturbances. Faster response delivered with excellent flow stability enable shorter process steps, stable chamber-gas delivery, higher accuracy, higher repeatability and a wide, multi-gas control range. The result is optimized process performance and maximized yields.

Further, the PI-980 MFC enhances overall system cost of ownership by eliminating the need for a number of traditional, costly gas-panel components. Its multi-gas, multi-range functionality dramatically reduces inventory requirements.

Steve Rhoades, executive vice president, Products and Operations, noted, "Our new PI-980 MFCs with NeuralStep technology are a

best-in-class addition to Aera's world renowned line of MFCs. This is a great example of AE's continuing commitment to technology innovation. It's also a great example of AE's continuing commitment to increasing our customers' competitive advantage."

#### About Advanced Energy

Advanced Energy is a global leader in the development and support of technologies critical to high-technology manufacturing processes used in the production of semiconductors, flat panel displays, data storage products, compact discs, digital video discs, architectural glass and other advanced product applications.

Leveraging a diverse product portfolio and technology leadership, AE creates solutions that maximize process impact, improve productivity and lower cost of ownership for its customers. This portfolio includes a comprehensive line of technology solutions in power, flow management, thermal instrumentation and plasma and ion beam sources for original equipment manufacturers (OEMs) and end-users around the world.

AE operates in regional centers in North America, Asia and Europe and offers global sales and support through direct offices, representatives and distributors. Founded in 1981, AE is a publicly held company traded on Nasdaq National Market under the symbol AEIS. More information can be found at [www.advanced-energy.com](http://www.advanced-energy.com)

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Web site: <http://www.advanced-energy.com>

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